

Title (en)

PLASMA GENERATION DEVICE AND PLASMA PROCESSING METHOD

Title (de)

PLASMAERZEUGUNGSVORRICHTUNG UND PLASMAVERARBEITUNGSVERFAHREN

Title (fr)

DISPOSITIF DE GÉNÉRATION DE PLASMA ET PROCÉDÉ DE TRAITEMENT PAR PLASMA

Publication

EP 4050973 A4 20221109 (EN)

Application

EP 19950060 A 20191022

Priority

JP 2019041419 W 20191022

Abstract (en)

[origin: EP4050973A1] A plasma generation device includes a device main body in which a reaction chamber for plasmatizing a processing gas is formed, at least one discharge path connected to the reaction chamber, a diffusion chamber connected to the at least one discharge path, and multiple ejection paths that are connected to the diffusion chamber and eject a plasma gas plasmatized in the reaction chamber having a taper surface formed in an opening of at least one ejection path among the multiple ejection paths to the diffusion chamber.

IPC 8 full level

H05H 1/46 (2006.01)

CPC (source: EP)

H05H 1/466 (2021.05)

Citation (search report)

- [YA] WO 2017056185 A1 20170406 - FUJI MACHINE MFG [JP]
- [YA] EP 3432691 A1 20190123 - FUJI CORP [JP]
- [A] DE 102016125699 A1 20180628 - PLASMATREAT GMBH [DE]
- [A] EP 3197245 A1 20170726 - FUJI MACHINE MFG [JP]
- [A] WO 2019150447 A1 20190808 - FUJI CORP [JP]
- See references of WO 2021079420A1

Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)

BA ME

Designated validation state (EPC)

KH MA MD TN

DOCDB simple family (publication)

EP 4050973 A1 20220831; EP 4050973 A4 20221109; CN 114586473 A 20220603; JP 7133724 B2 20220908; JP WO2021079420 A1 20210429; WO 2021079420 A1 20210429

DOCDB simple family (application)

EP 19950060 A 20191022; CN 201980101498 A 20191022; JP 2019041419 W 20191022; JP 2021553194 A 20191022